

Fig. 2.4 The percentage decomposition versus temperature for 5% concentration of AsH₃ in various ambient with different surfaces.

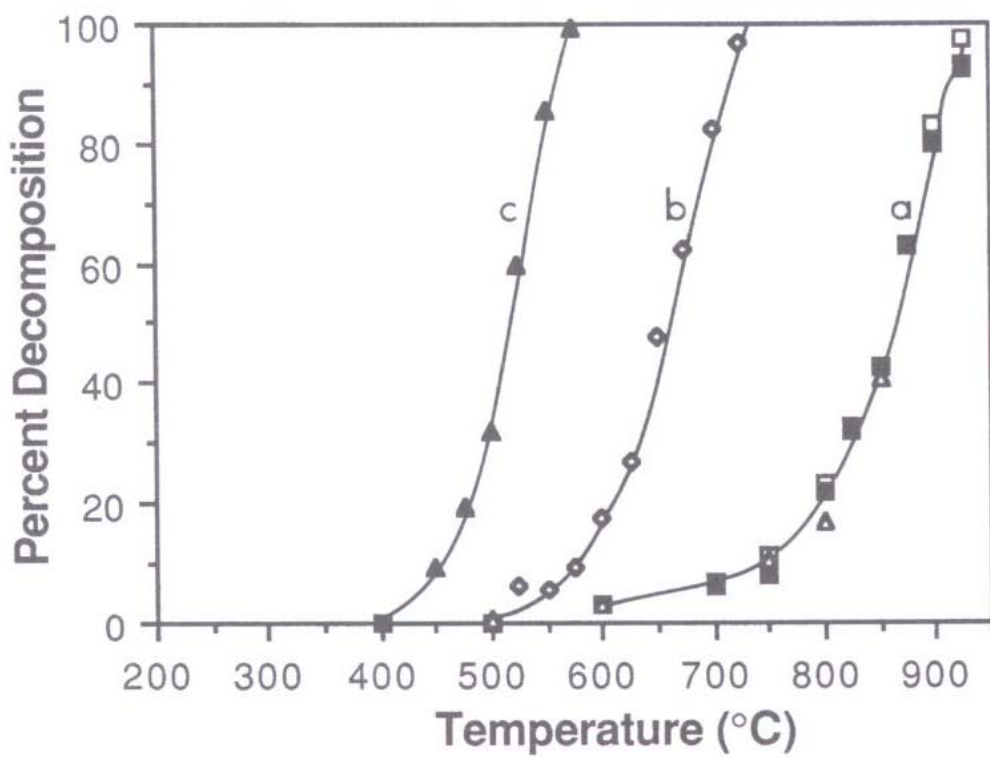


Fig. 2.5 The dependence of PH₃ pyrolysis on different carrier gases and different type of surfaces.

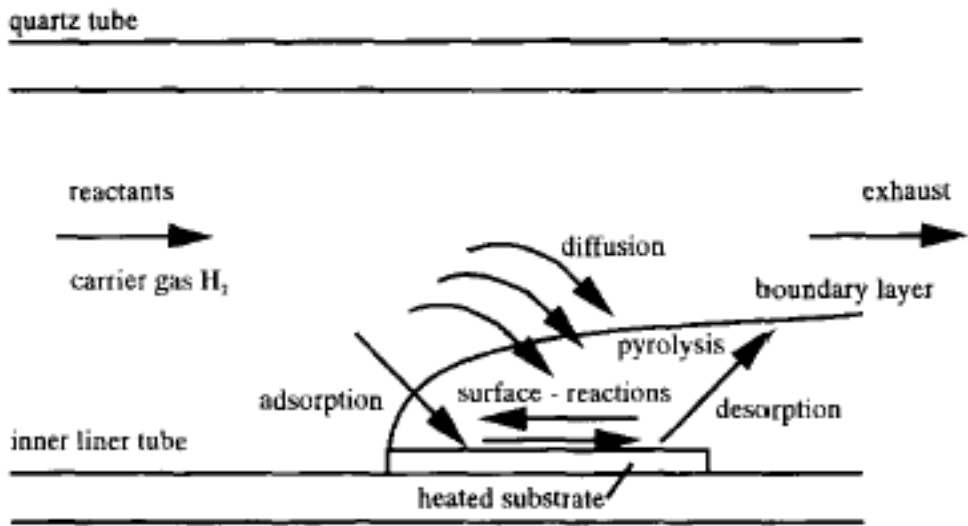


Fig. 2.6 The overall MOCVD growth process.

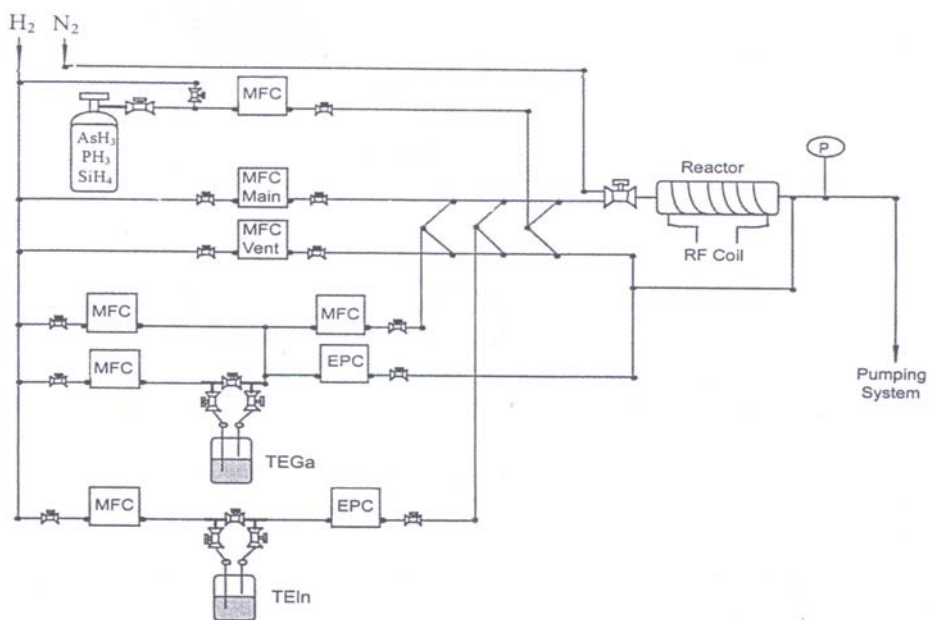
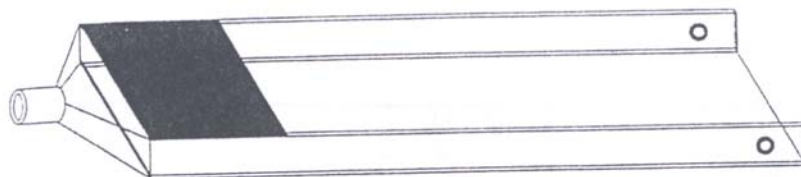
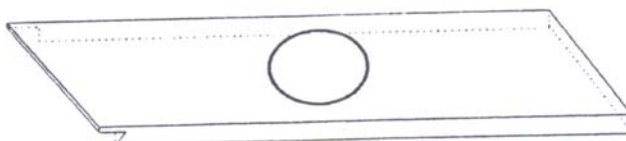


Fig 2.7 The schematic diagram of the MOCVD system in this study.



(a) Reactor



(b) Susceptor



(c) Exterior reactor

Fig. 2.8 The schematic diagram of the reactor system used in this study including the geometry of the reactor and the susceptor.

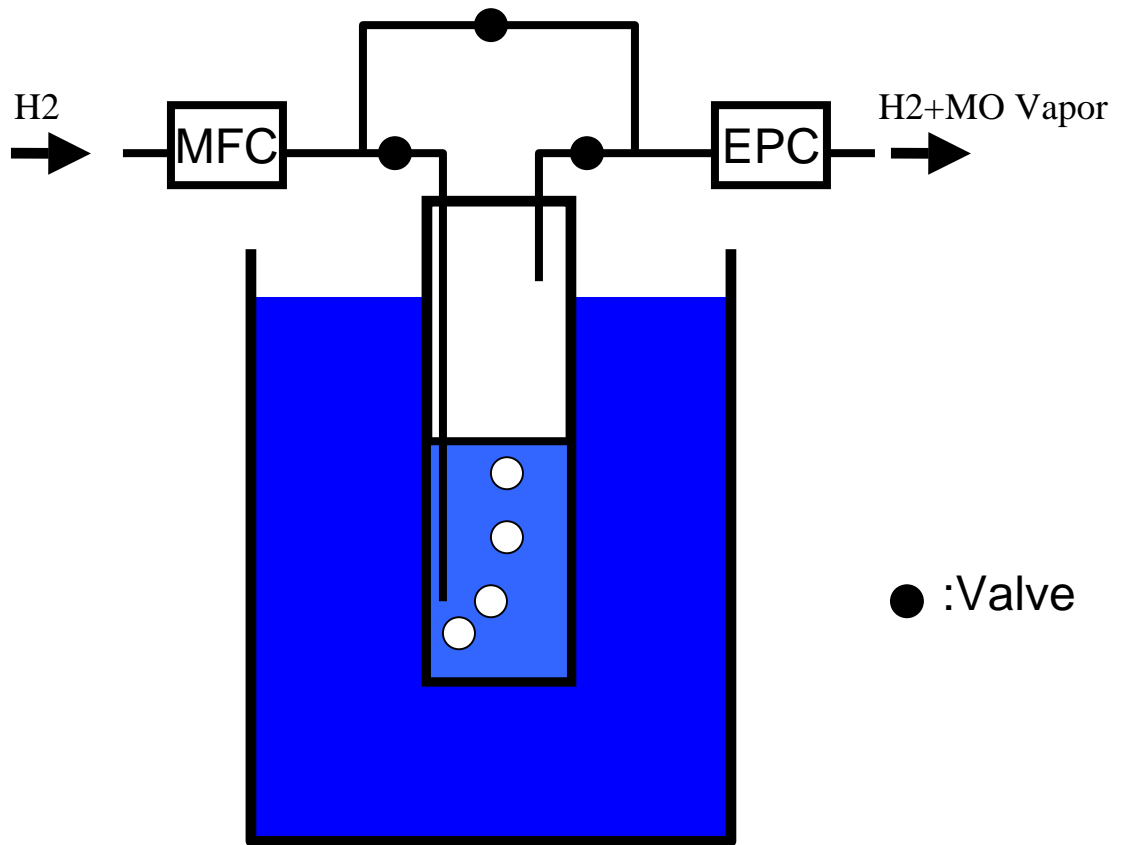


Fig. 2.9 The schematic diagram of the bubbler and bath tank.